**Product Specification** 

1003.306301

Part Number		Customer				
Category		Parameter	Specification	Measurement Method		
OverallWafer	1.0	Diameter	150.00 +/- 0.50 mm	WaferVendor		
	2.0	Primary Flat Length	57.50 +/- 2.50 mm	Wafer Vendor		
	3.0	Primary Flat Orientation	{110}+/- 0.5 degree	Wafer Vendor		
	4.0	Growth Method	CZ	Wafer Vendor		
	5.0	Туре	Any	Wafer Vendor		
	6.0	Dopant	any	Wafer Vendor		
	7.0	Resistivity	1 - 100 ohm cm	Wafer Vendor		
	8.0	Overall Thickness	345.00 +/- 5.00 um	Wafer Vendor		
	9.0	Total Thickness Variation (TTV)	<5.00um	Guaranteed by process		
HandleSilicon	9.1	Handle Thickness	345.00 +/- 5.00 um	ADE measurement		
OverallWafer	9.2	Bow	<80.00um	ADE measurement		
	9.3	Warp	<80.00um	ADE measurement		
	10.0	Orientation	<100> +/-0.5	Wafer Vendor		
	11.0	Back Surface Quality	Polished with laser mark	Wafer Vendor		
	12.0	Front Surface Quality	Prime	Wafer Vendor		
	13.0	Edge Chips	None	Bright Light 100% (note 2)		
DeviceSilicon	15.0	Haze	None	Bright Light, 100% (note 2).		
	16.0	Scratches	None	Bright Light, 100% (note 2).		

Icemos Technology Ltd

**Product Specification** 

1003.306301

Part Number		Customer		
Category	Parameter	Specification	Measurement Method	
Shipping Details Wafer per box : Max 25		Max 25		
	Packaging :	Taped Polypropylene Wafer Box Empak, Ultrapak, 150.00mm Antistatic Double Bagging		
	Lot Shipment Data	Device Thickness Bow / Warp Data Handle and SOI Thickness		
Explanatory Notes	1. Microscope inspection performed using microscope scan as below. 5x objective.			

2. All bright light inspections performed exclude all wafer area outside the edge exclusion defined in Overall Wafer, Edge Exclusion. High intensity bright lamp inspection as per ASTM F523.

3. 9 point measurement are as shown in the diagram below:



Additional Information